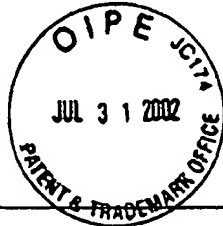


**INFORMATION DISCLOSURE
CITATION IN AN
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(PTO-1449)

ATTY. DOCKET NO.
6301/Consilium/DV

SERIAL NO.
09/928,474

APPLICANT
Badri N. KRISHNAMURTHY et al.

FILING DATE
August 14, 2001

GROUP
2171

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AS	09/927,444	Ward et al.	Dynamic Control of Wafer Processing Paths in Semiconductor Manufacturing Processes			08/13/01
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EXAMINER'S INITIALS	PATENT/ PUBLICATION NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
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AS	Zhou, Zhen-Hong and Rafael Reif. August 1995. "Epi-Film Thickness Measurements Using Emission Fourier Transform Infrared Spectroscopy—Part II: Real-Time <i>in Situ</i> Process Monitoring and Control." IEEE Transactions on Semiconductor Manufacturing, Vol. 8, No. 3.
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AS	2,050,247	08/29/91	Canada			X	
	2,165,847	08/29/91	Canada			X	
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	05-151231	06/18/93	Japan				X
	05-216896	08/27/93	Japan				X
	05-266029	10/15/93	Japan				X
	06-110894	04/22/94	Japan				X
	06-176994	06/24/94	Japan				X
	06-252236	09/09/94	Japan				X
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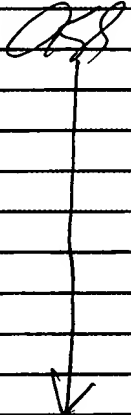
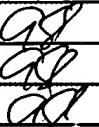
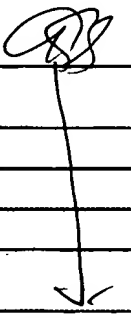

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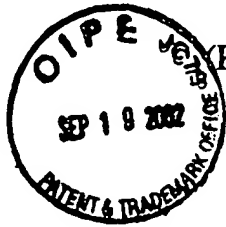
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				APPLICANT Badri N. KRISHNAMURTHY Technology Center 2100			
				FILING DATE August 14, 2001		GROUP 2171	
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	11-135601	05/21/99	Japan			Yes	No
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	6,112,130	08/29/00	Fukuda et al.			10/01/97
	6,148,246	11/14/00	Kawazome			06/10/98

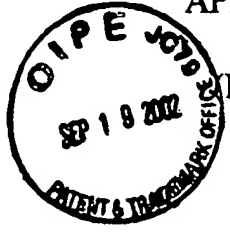

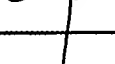
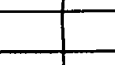
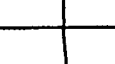
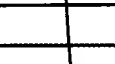
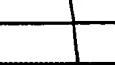

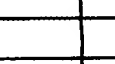
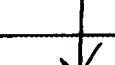
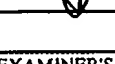
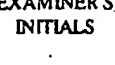
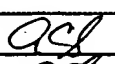

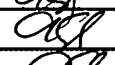
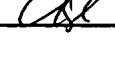




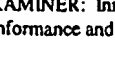

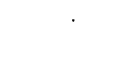

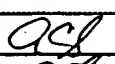

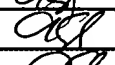
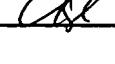




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						Yes	No
OJ	0 747 795 A2	12/11/96	Europe			X	
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	11-126816	05/11/99	Japan				X

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<i>Anda Stevens</i>	02-25-05

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION 				ATTY. DOCKET NO. 6301/Consilium/DV		SERIAL NO. 09/928,474 RECEIVED SEP 20 2002	
(PTO-1449)				APPLICANT Badri N. KRISHNAMURTHY et al.			
FILING DATE August 14, 2001				GROUP 2171			
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
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	0 621 522 A2	10/26/94	Europe			X	
	8-50161	02/20/96	Japan				X
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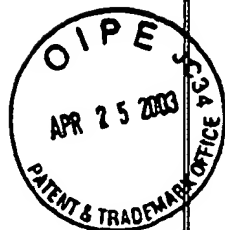
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APPLICANT
Badri N. KRISHNAMURTHY et al.

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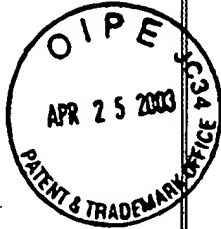
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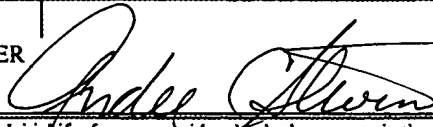
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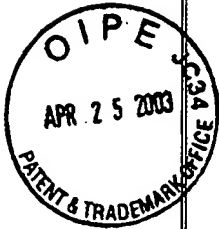
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	6,097,887	08/01/00	Hardikar et al.			10/27/97
	6,108,092	08/22/00	Sandhu			06/08/99
	6,127,263	10/03/00	Parikh			07/10/98
	6,136,163	10/24/00	Cheung et al.			03/05/99
	6,141,660	10/31/00	Bach et al.			07/16/98
	6,143,646	11/07/00	Wetzel			06/03/97
	6,148,099	11/14/00	Lee et al.			07/03/97
✓	6,148,239	11/14/00	Funk et al.			12/12/97

EXAMINER

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**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION
(PTO-1449)**

ATTY. DOCKET NO.
006301
USA/Consilium/Consilium

SERIAL NO.
09/028,474

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Technology Center 2100

APPLICANT
Badri N. KRISHNAMURTHY et al.

FILING DATE
August 14, 2001

GROUP
2171



U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>CR</i>	3,205,485	09/07/65	Noltingk			10/21/60
	3,229,198	01/11/66	Libby			09/28/62
	4,000,458	12/28/76	Miller et al.			08/21/75
	4,302,721	11/24/81	Urbanek et al.			05/15/79
	4,750,141	06/07/88	Judell et al.			11/26/85
	4,757,259	07/12/88	Charpentier			11/05/86
	4,938,600	07/03/90	Into			02/09/89
	5,283,141	02/01/94	Yoon et al.			03/05/92
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	5,642,296	06/24/97	Saxena			07/29/93
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EXAMINER

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 006301 USA/Consilium/Consilium/ DK		SERIAL NO. 09/928,474	
				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2812	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
↓	3,767,900	10/23/73	Chao et al.			06/23/71	
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	4,616,308	10/07/86	Morshedi et al.			12/02/85	
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	5,519,605	05/21/96	Cawlfeld			10/24/94	
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	FOREIGN PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
↓	EP 1 067 757	01/10/01	Europe			X	
	WO 01/33277	05/10/01	WO			X	
	WO 02/31613 A2	04/18/02	WO			X	
	WO 02/31613 A3	04/18/02	WO			X	
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EXAMINER 				DATE CONSIDERED 02-28-05			

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SHEET 1 OF 1

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				FILING DATE August 14, 2001		GROUP 2812	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 99/59200 ✓	11/18/99	WIPO			X	
	WO 01/52319 ✓	07/19/01	WIPO			X	
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	Williams, Randy, Dadi Gudmundsson, Kevin Monahan, Raman Nurani, Meryl Stoller and J. George Shanthikumar. October 1999. "Optimized Sample Planning for Wafer Defect Inspection," <i>Semiconductor Manufacturing Conference Proceedings, 1999 IEEE International Symposium on Santa Clara, CA</i> . Piscataway, NJ. pp. 43 - 46.						
	23 July 2003. Invitation to Pay Additional Fees and Communication Relating to the Results of the Partial International Search for PCT/US02/19116.						
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EXAMINER 				DATE CONSIDERED 07-25-05			

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SHEET 2 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 006301 USA/Consilium/Consilium/ DK		SERIAL NO. 09/928,474	
				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2812	
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation Yes No	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
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EXAMINER 				DATE CONSIDERED 02-25-05			

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SHEET 1 OF 2

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				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2812	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
OKA	4,207,520	06/10/80	Flora et al.			04/06/78	
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	4,609,870	09/02/86	Lale et al.			09/13/84	
	4,755,753	07/05/88	Chern			07/23/86	
	5,427,878	06/27/95	Corliss			05/16/94	
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	5,867,389	02/02/99	Hamada et al.			11/26/96	
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	6,271,670	08/07/01	Caffey			02/08/99	
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
CSA AS	WO 01/11679	02/15/01	WIPO			X	
	WO 01/080306	10/25/01	WIPO			X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
RS RS RS	Miller, G. L., D. A. H. Robinson, and J. D. Wiley. July 1976. "Contactless measurement of semiconductor conductivity by radio frequency-free-carrier power absorption." <i>Rev. Sci. Instrum.</i> , Volume 47, No. 7. pp. 799 - 805.						
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	2000. "Microsense II Capacitance Gaging System." www.adetech.com .						
EXAMINER <i>Andee C. Schuman</i>			DATE CONSIDERED 02-25-05				

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)



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GROUP
2812

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
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	Rocha, Joao and Carlos Ramos. September 12, 1994. "Task Planning for Flexible and Agile Manufacturing Systems." <i>Intelligent Robots and Systems '94. Advanced Robotic Systems and the Real World, IROS '94. Proceedings of the IEEE/RSJ/GI International Conference on Munich, Germany 12-16 Sept. 1994.</i> New York, New York: IEEE. pp. 105-112.
	March 15, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.
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	August 8, 2003. International Search Report for PCT/US03/08513.
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	December 11, 2003. Office Action for U.S. Serial No. 09/943,383, filed August 31, 2001.
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	February 2, 2004. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.

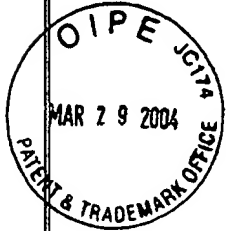
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
OK	4,901,218	02/13/90	Cornwell			03/04/88
	5,427,878	06/27/95	Corliss			05/16/94
	5,761,065	06/02/98	Kittler et al.			03/30/95
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EXAMINER	DATE CONSIDERED					
<i>Under Review</i>	02-25-05					

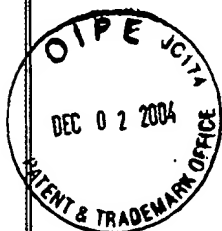
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<p align="center">INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</p> <p>PTO DEC 02 2004 PATENT & TRADEMARK OFFICE</p>	<p>ATTY. DOCKET NO. 006301 USA/ Consilium/Consilium</p>	<p>SERIAL NO. 09/928,474</p>
	<p>APPLICANT Badri N. KRISHNAMURTHY et al.</p>	
	<p>FILING DATE August 14, 2001</p>	<p>GROUP 2812</p>
<p align="center">OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</p>		
<p><i>QJ</i></p>	<p>November 17, 2004. Written Opinion for PCT Serial No. PCT/US01/27407.</p>	
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<p>EXAMINER <i>Quida C. Alvarez</i></p>	<p>DATE CONSIDERED <i>02-25-05</i></p>	

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Consilium/Consilium

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AS	4,974,543	12/04/90	Jansen			02/28/86
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
AS	WO 01/01205 A2	01/04/01	WIPO			X	
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	Cruden, Brett et al. "Chemical Vapor Deposition (CVD) of Teflon & trade-like Films for Use in Low-k Interlayer Dielectric Applications." http://plasma-processing.com/chemvap .
	Kim, Jiyoun et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre-and Post-Measurement Strategy." <i>University of Michigan, Electrical Engineering and Computer Science Department</i> .
	November 11, 2004. International Search Report for PCT Serial No. PCT/US03/36501.

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(PTO-1449)

ATTY. DOCKET NO.
6301/Consilium/DV

SERIAL NO.
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APPLICANT
Badri N. KRISHNAMURTHY, et al.

FILING DATE
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2171

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
 	 	 	 	 	 	
 	 	 	 	 	 	
 	 	 	 	 	 	

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT/ PUBLICATION NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
 	 	 	 	 	 	 	
 	 	 	 	 	 	 	

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	Boning, Duane, William Moyne, Taber Smith, James Moyne, Roland Telfeyan, Arnon Hurwitz, Scott Shellman, and John Taylor. October 1996. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans. CPMT (C)</i> , Vol. 19, No. 4, pp. 307-314.
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EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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